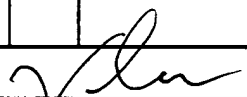


Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number.

[illegible]

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)			
LV		Songlin Xu et al., "Wall-dependent etching characteristics of organic antireflection coating in O <sub>2</sub> +halogen/hydrogen halide plasma", J.Vac Sci. Technol. A 19(6), Nov/Dec 2001	
LV		Songlin Xu et al., "Gate Oxide Integrity Issue Cause by Wall-Related Process Drivt in Plasma Etching", 2002 7 <sup>th</sup> International Symposium on Plasma-and Process-Induced Damage June 6-7, Maui HI, USA	
LV		Songlin Xu et al., "Characteristics and mechanism of etch process sensitivity to chamber surface condition", J. Vac. Sci. Technol. B19(1), Jan/Feb 2001	
Examiner Signature		Date Considered	4/11/05

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov) or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.